

8. (Amended) A method for operating an optically recordable disk memory comprising the steps of:

introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less;

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

15. (Amended) A method for operating an optically recordable disk memory comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

22. (Amended) A method for operating an optically recordable disk memory comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is $30/\text{mm}^2$ or less;
wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

29. (Amended) A method for operating an optically recordable disk memory comprising the steps of:

introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500\AA or less;

irradiating a laser light having a wavelength of 700 to 800 nm onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is $30/\text{mm}^2$ or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

36. (Amended) A method for operating an optically recordable disk memory comprising the steps of:

introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500\AA or less;

irradiating a laser light having a wavelength of 700 to 800 nm onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is $30/\text{mm}^2$ or less;

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

43. (Amended) A method for operating an optically recordable disk memory comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a

hard-carbon coating having a thickness of 500Å or less;
irradiating a laser light having a wavelength of 700 to 800 nm onto said substrate through said hard-carbon coating;
wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;
wherein said hard-carbon coating contains silicon and phosphorus.

50. (Amended) A method for operating an optically recordable disk memory comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a laser light having a wavelength of 700 to 800 nm onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less;

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

57. (Amended) A method for operating an optically recordable disk memory comprising the steps of:

introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a visible light onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

58. (Amended) A method for operating an optically recordable disk memory comprising the steps of:

introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a visible light onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less;

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

59. (Amended) A method for operating an optically recordable disk memory comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a visible light onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

60. (Amended) A method for operating an optically recordable disk memory comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a visible light onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or

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less;

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cont. wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

68. (Amended) A method of operating an optical magnetic disk comprising the steps of:

introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

69. (Amended) A method of operating an optical magnetic disk comprising the steps of:

G10 introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less,

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

70. (Amended) A method of operating an optical magnetic disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is $30/\text{mm}^2$ or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

71. (Amended) A method of operating an optical magnetic disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500\AA or less;

irradiating a semiconductor laser light onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is $30/\text{mm}^2$ or less;

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

79. (Amended) A method of operating an optical magnetic disk comprising the steps of:

introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500\AA or less;

irradiating a laser light having a wavelength of 700 to 800 nm onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is $30/\text{mm}^2$ or less and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

80. (Amended) A method of operating an optical magnetic disk comprising the steps of:

introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a laser light having a wavelength of 700 to 800 nm onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less,

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

81. (Amended) A method of operating an optical magnetic disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a laser light having a wavelength of 700 to 800 nm onto said substrate through said hard-carbon coating,

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

82. (Amended) A method of operating an optical magnetic disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a laser light having a wavelength of 700 to 800 nm onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less;

wherein said hard-carbon coating contains silicon and phosphorus at a

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cont. concentration at 20 atomic% or less.

90. (Amended) A method of operating an optical magnetic disk comprising the steps of:

introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a visible light onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

91. (Amended) A method of operating an optical magnetic disk comprising the steps of:

G12 introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a visible light onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less,

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

92. (Amended) A method of operating an optical magnetic disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a visible light onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is $30/\text{mm}^2$ or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

93. (Amended) A method of operating an optical magnetic disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500\AA or less;

irradiating a visible light onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is $30/\text{mm}^2$ or less;

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

101. (Amended) A method of operating a compact disk comprising the steps of:

introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500\AA or less;

irradiating a semiconductor laser light onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is $30/\text{mm}^2$ or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

102. (Amended) A method of operating a compact disk comprising the steps of:

introducing an optical disk having a surface protected by a protective film

comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less,

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

103. (Amended) A method of operating a compact disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

104. (Amended) A method of operating a compact disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less;

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

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112. (Amended) A method of operating a compact disk comprising the steps of:

introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a laser light having a wavelength of 700 to 800 nm onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

113. (Amended) A method of operating a compact disk comprising the steps of:

introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a laser light having a wavelength of 700 to 800 nm onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less,

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

114. (Amended) A method of operating a compact disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a laser light having a wavelength of 700 to 800 nm onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or

less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

115. (Amended) A method of operating a compact disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a laser light having a wavelength of 700 to 800 nm onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less;

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

123. (Amended) A method of operating a compact disk comprising the steps of:

introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a visible light onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

124. (Amended) A method of operating a compact disk comprising the steps of:

introducing an optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a visible light onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is $30/\text{mm}^2$ or less,

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

125. (Amended) A method of operating a compact disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500\AA or less;

irradiating a visible light onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is $30/\text{mm}^2$ or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

126. (Amended) A method of operating a compact disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500\AA or less;

irradiating a visible light onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is $30/\text{mm}^2$ or less;

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

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134. (Amended) A method of operating an optical disk comprising the steps of:

introducing said optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

135. (Amended) A method of operating an optical disk comprising the steps of:

introducing said optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less,

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

136. (Amended) A method of operating an optical disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

137. (Amended) A method of operating an optical disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a semiconductor laser light onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less;

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

145. (Amended) A method of operating an optical disk comprising the steps of:

introducing said optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a laser light having a wavelength of 700 to 800 nm onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

146. (Amended) A method of operating an optical disk comprising the steps of:

introducing said optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a laser light having a wavelength of 700 to 800 nm onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is $30/\text{mm}^2$ or less,

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

147. (Amended) A method of operating an optical disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500\AA or less;

irradiating a laser light having a wavelength of 700 to 800 nm onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is $30/\text{mm}^2$ or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

148. (Amended) A method of operating an optical disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500\AA or less;

irradiating a laser light having a wavelength of 700 to 800 nm into said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is $30/\text{mm}^2$ or less;

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

156. (Amended) A method of operating an optical disk comprising the steps of:

introducing said optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a visible light onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

157. (Amended) A method of operating an optical disk comprising the steps of:

introducing said optical disk having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a visible light onto said optical disk through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less,

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

158. (Amended) A method of operating an optical disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a visible light onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less, wherein said hard-carbon coating is an outermost layer of the disk, and wherein said hard-carbon coating contains hydrogen;

wherein said hard-carbon coating contains silicon and phosphorus.

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159. (Amended) A method of operating an optical disk comprising the steps of:

introducing a substrate made of an organic resin or an industrial plastic material, said substrate having a surface protected by a protective film comprising a hard-carbon coating having a thickness of 500Å or less;

irradiating a visible light onto said substrate through said hard-carbon coating;

wherein the number of pin-holes in said hard-carbon coating is 30/mm² or less;

wherein said hard-carbon coating contains silicon and phosphorus at a concentration at 20 atomic% or less.

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